



Chip-Backside Vulnerability to Side Channel Attacks Exploiting Intentional Electromagnetic Interference

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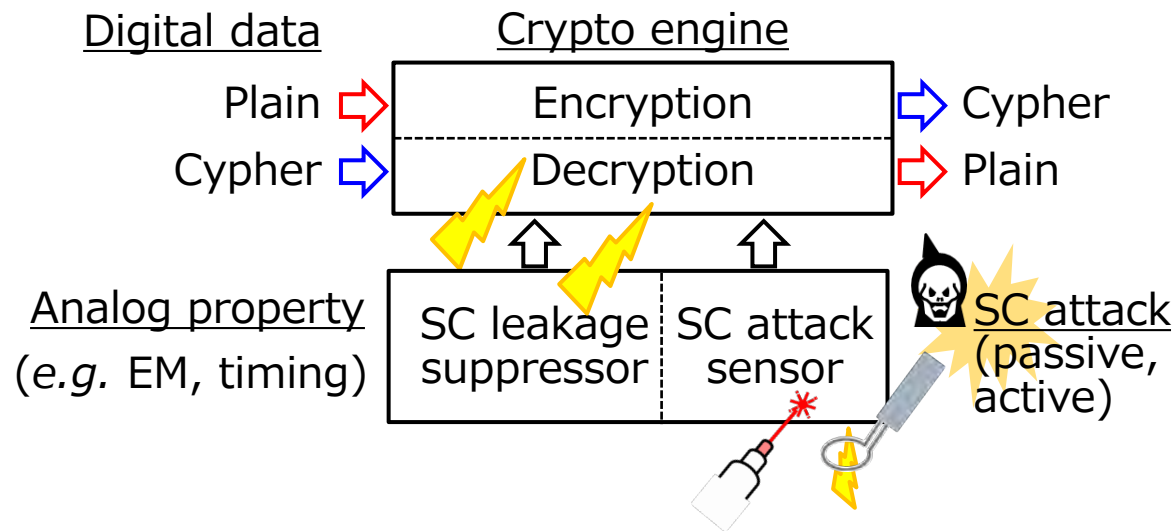
April 18th, 2025



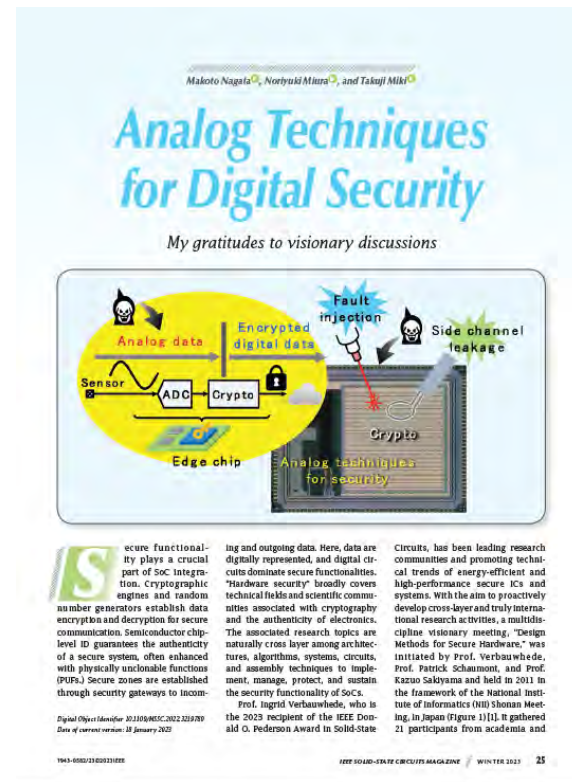
Outline

1. Introduction
2. Passive side channels from IC chip backside
3. Active fault injection on IC chip backside
4. Packaging for security
5. Summary

Analog techniques for digital security

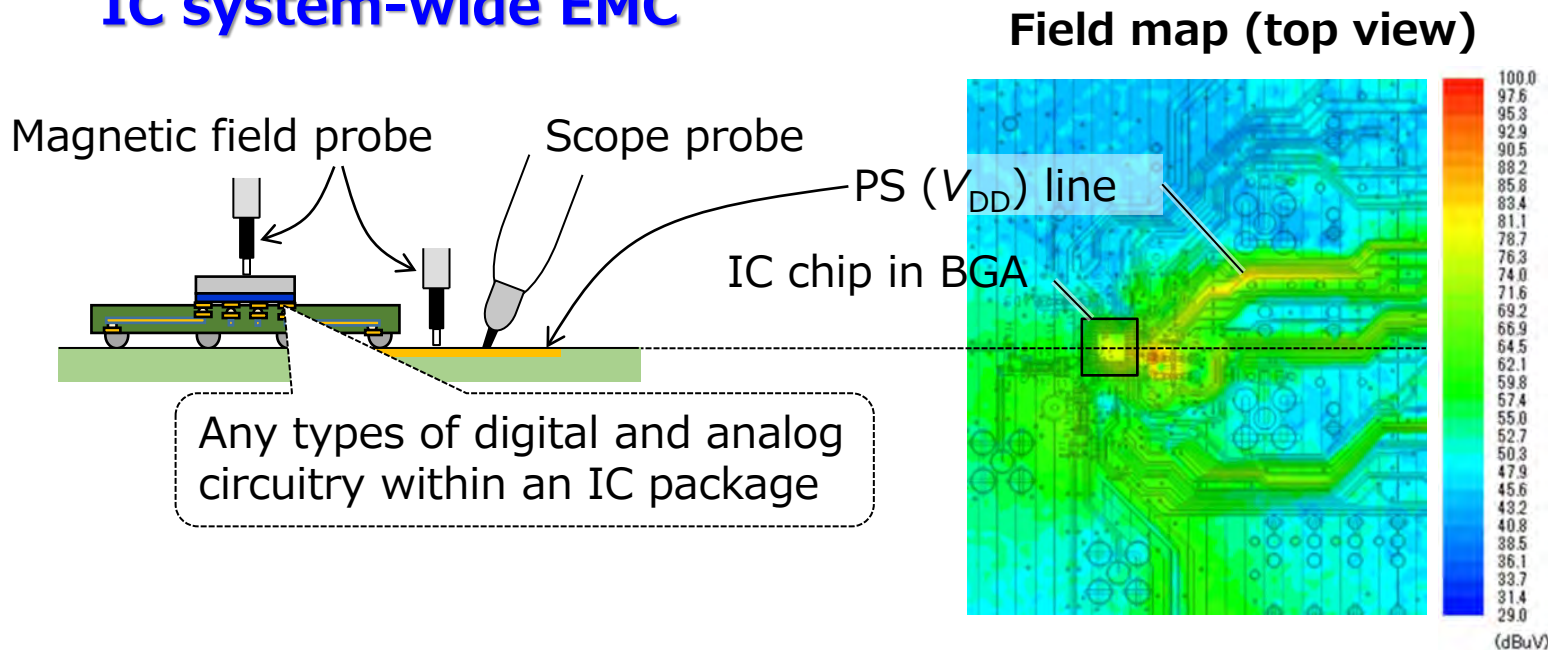


- ▶ Analog techniques at the levels of device, circuit, system, package and simulation protect digital security in IC chips.



Electromagnetic compatibility (EMC)

IC system-wide EMC



- ▶ EM noise and power noise from an IC chip are observable on its package and across a whole printed circuit board (PCB).

Relevance among EMC and HWS

EMI

- ▶ Electromagnetic emission → Side channel leakage (passive information leakage)
- ▶ EMI analysis → SCA analysis

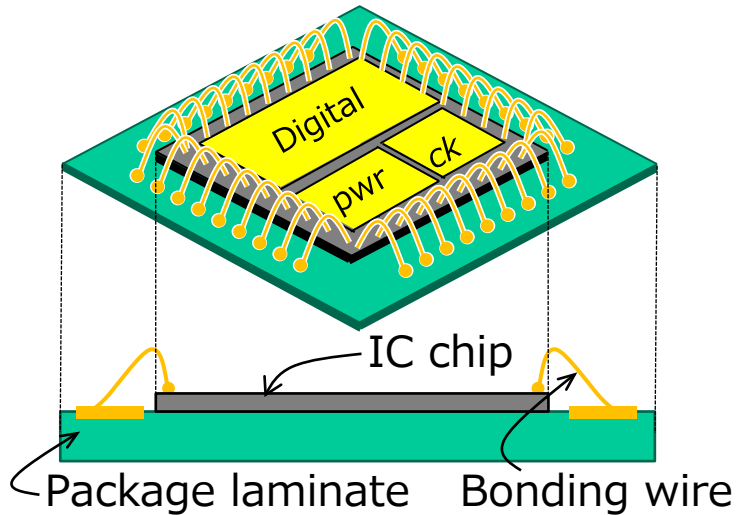
EMS

- ▶ Electromagnetic immunity → Fault injection (active information leakage)
- ▶ EMS analysis → Fault analysis

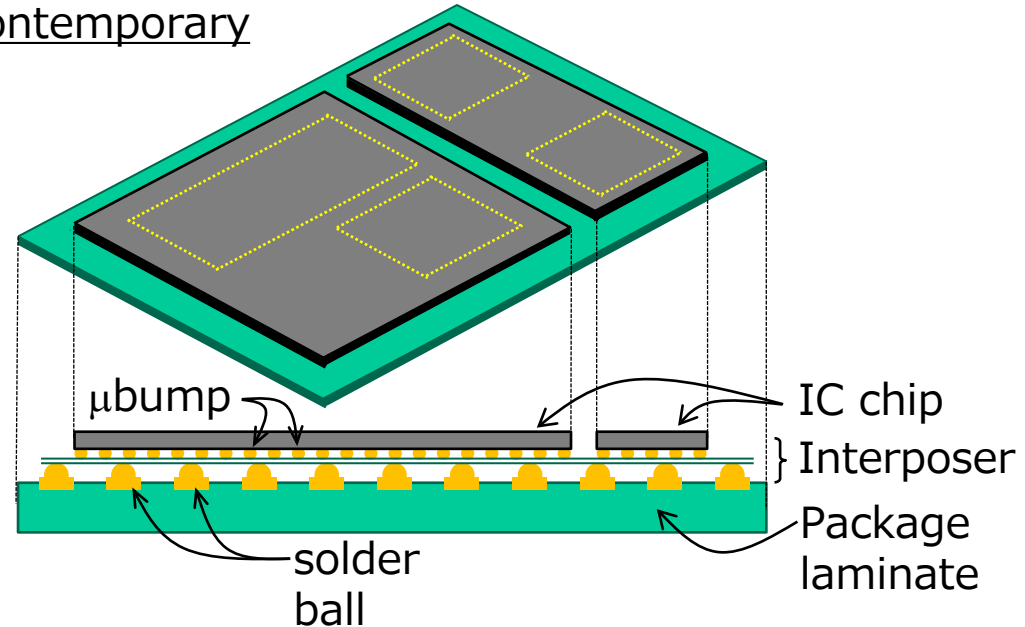
➡ **In-depth understandings of IC-chip level EMC, toward the quality design of IC chips for hardware security**

Face-up and flip-chip assembly

Traditional

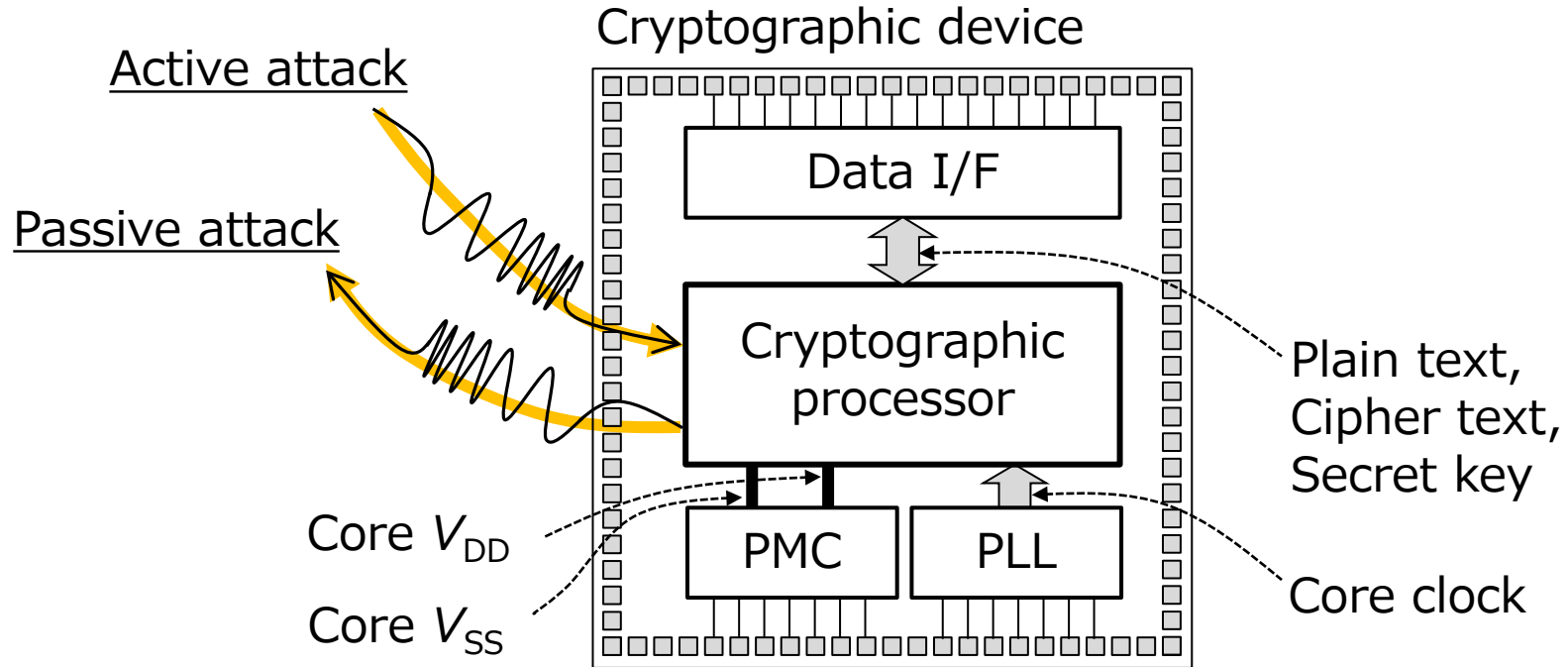


Contemporary



- ▶ Mega trends: flip chip on membrane interposer with multiple chip(lets)
- ▶ Silicon substrate backside is open for performance improvements (pros) while also for adversarial approaches (cons).

Physical isolation at IC chip level

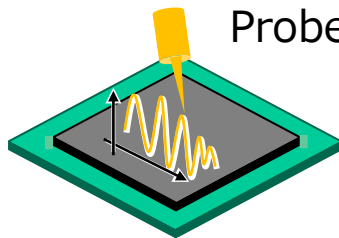


- Architectural explorations for securing horizontal data channels while circuit- and package-level countermeasures needed for vertical EM channels.

Outline

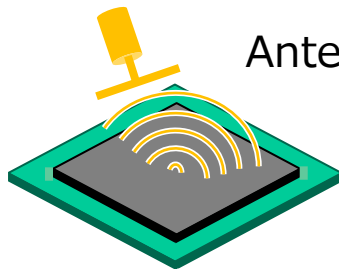
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Passive side channels on Si backside



Probe/needle

- ✓ Si substrate voltage
- ✓ Electric field



Antenna/coil

- ✓ EM waves
- ✓ Magnetic flux

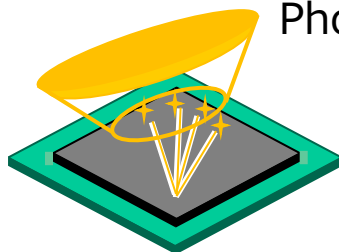
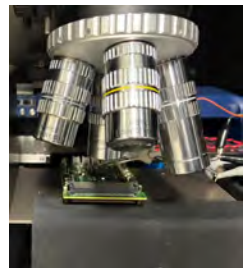
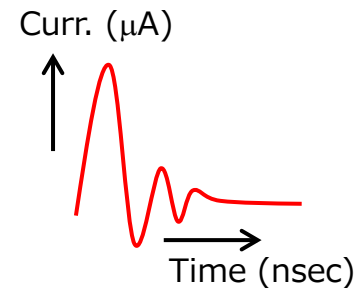


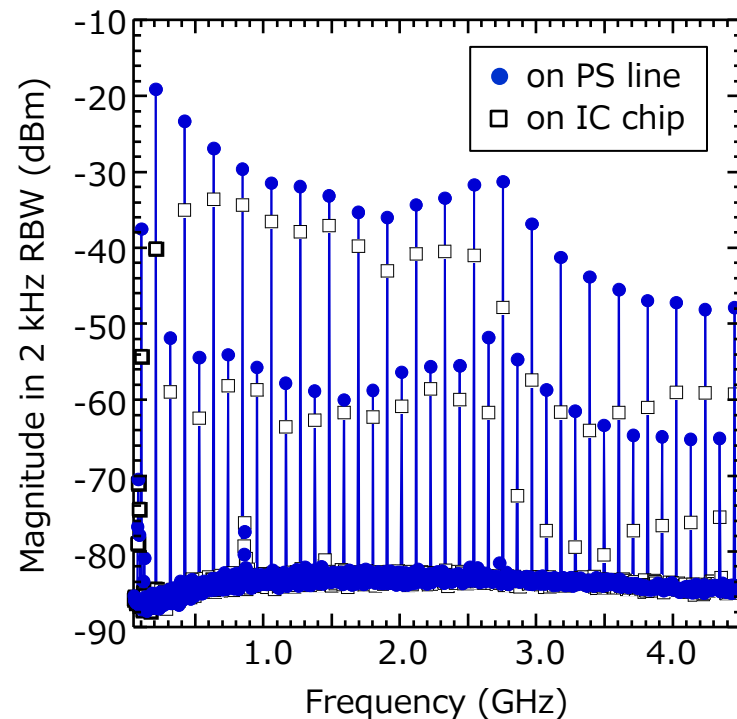
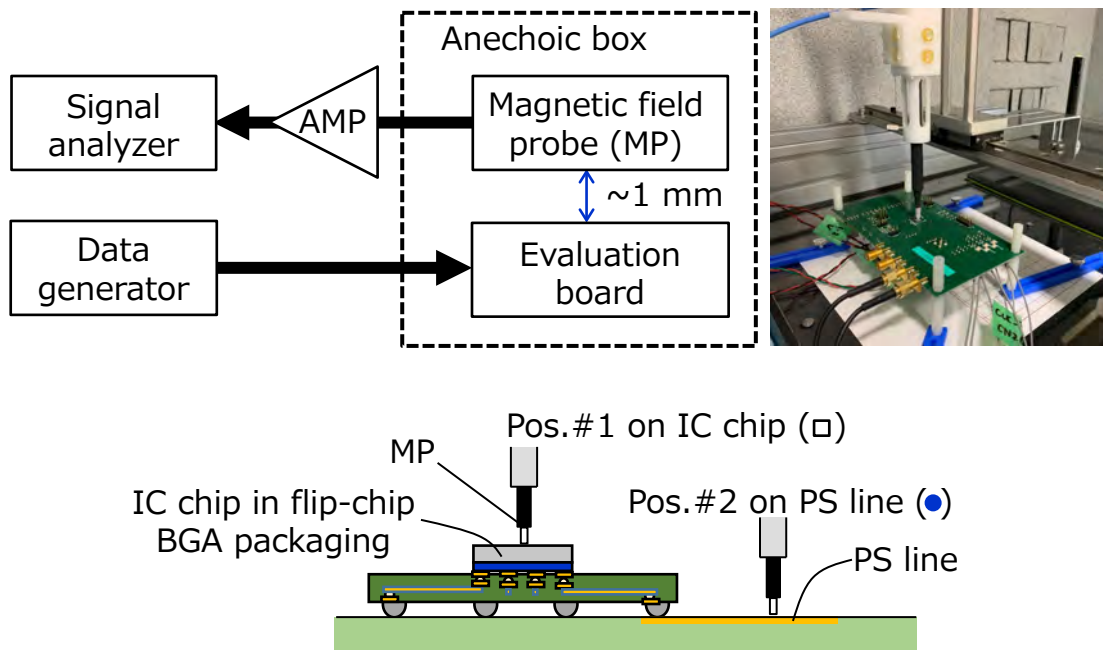
Photo sensor

- ✓ IR photons
- ✓ IR microscopy



**Matter of
power current**

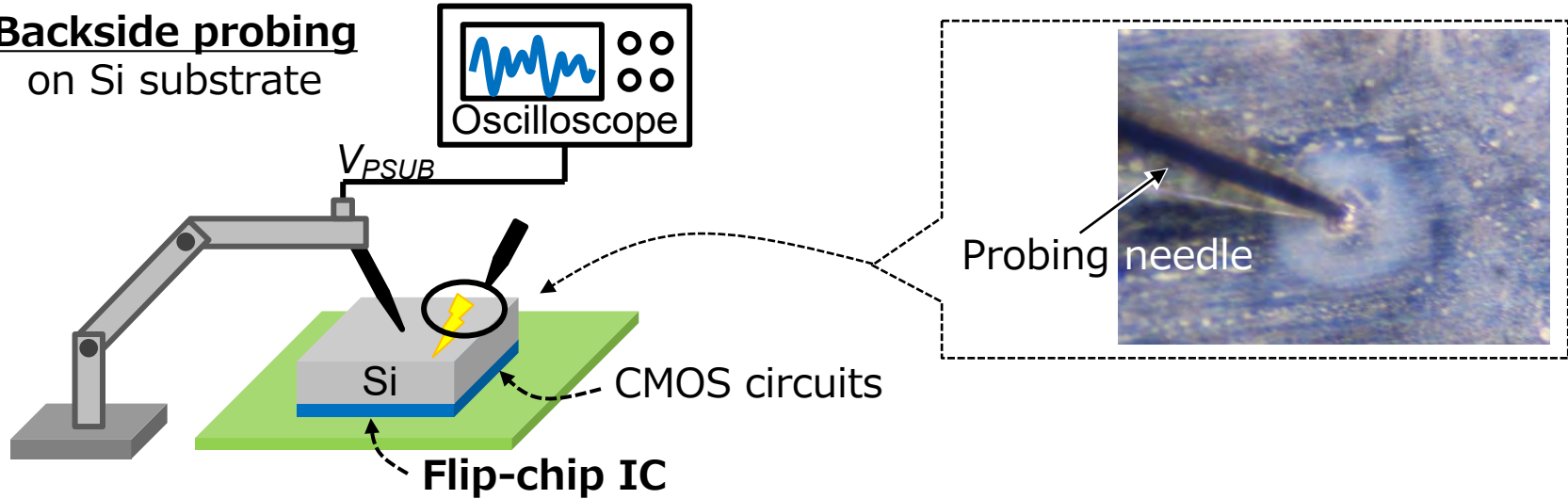
Electromagnetic (EM) emission by ICs



- ▶ **Near field magnetic coupling between an IC chip and an antenna** exhibits high order harmonics of digital clocking frequency (e.g. $106 \times n$ MHz.)

Si substrate voltage variation

Backside probing
on Si substrate

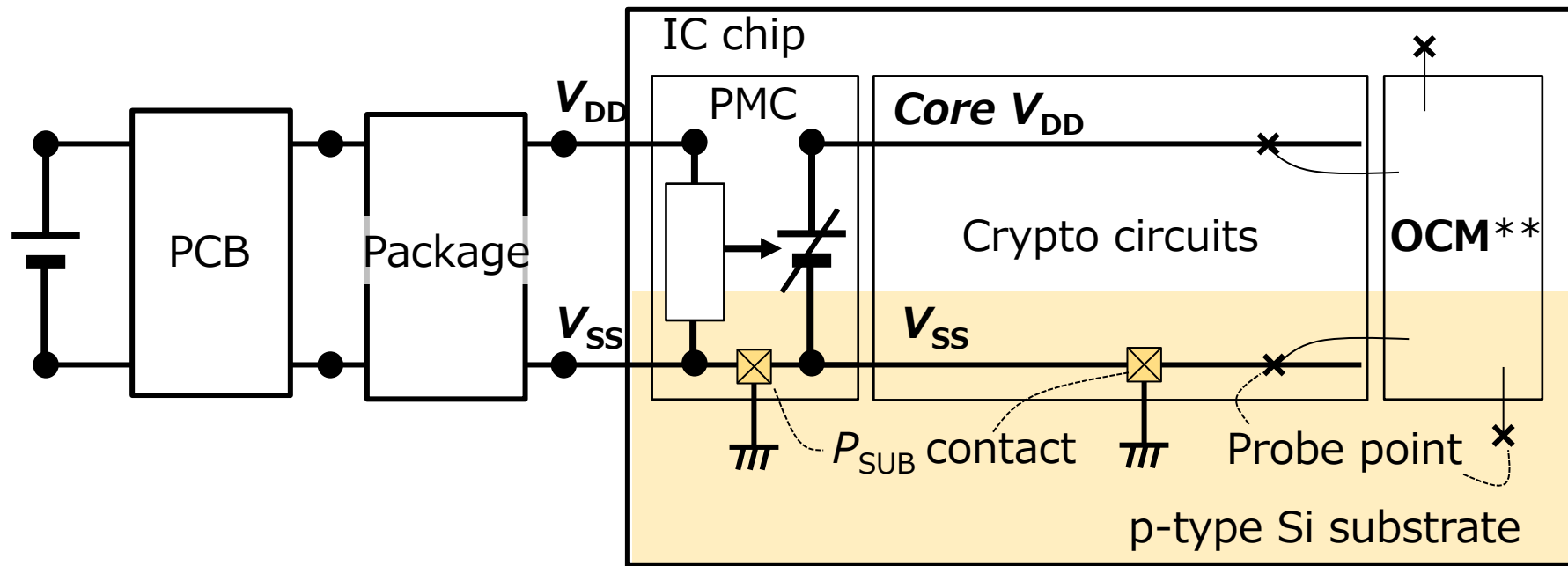


- ▶ **Direct voltage probing on Si substrate backside (=IC chip backside) with a metallic needle**

Si substrate as a part of PDN*

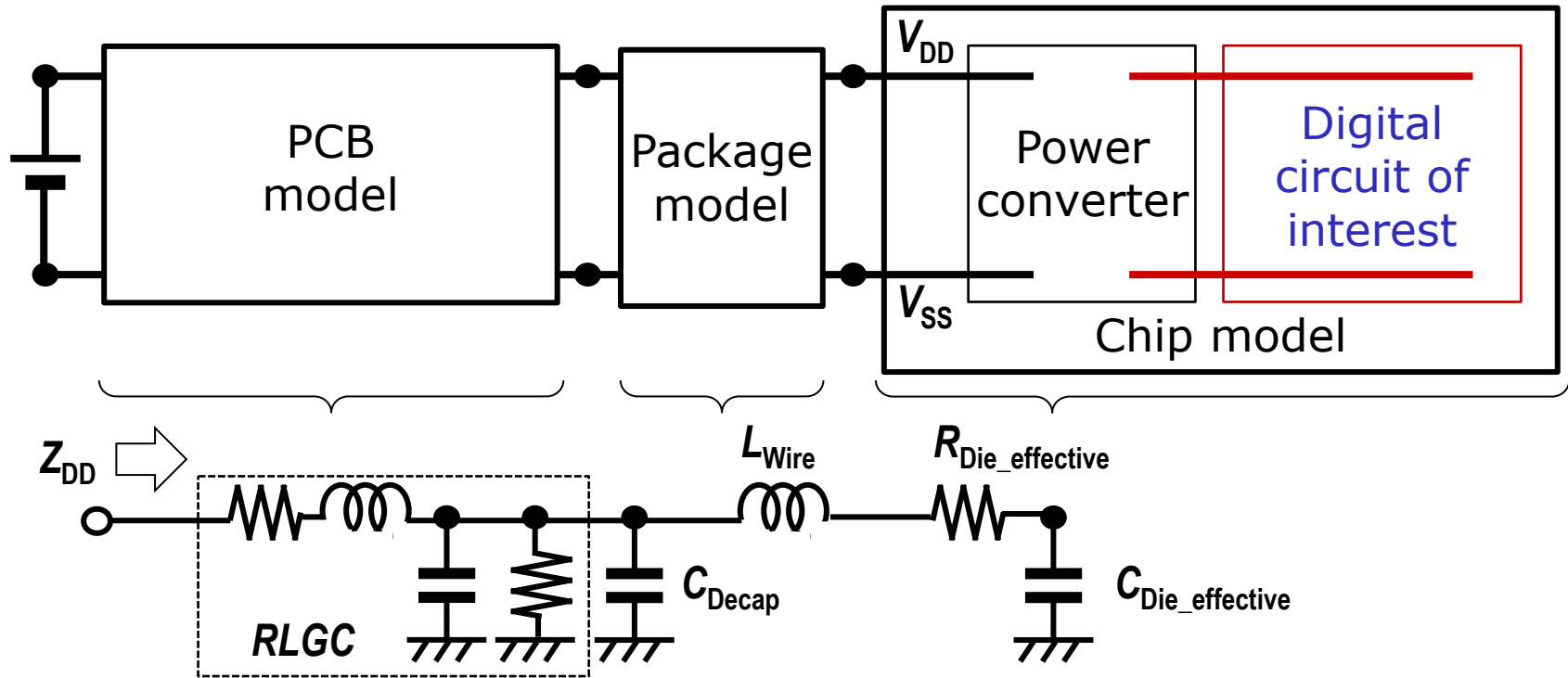
*Power delivery network

**On-chip monitor circuit



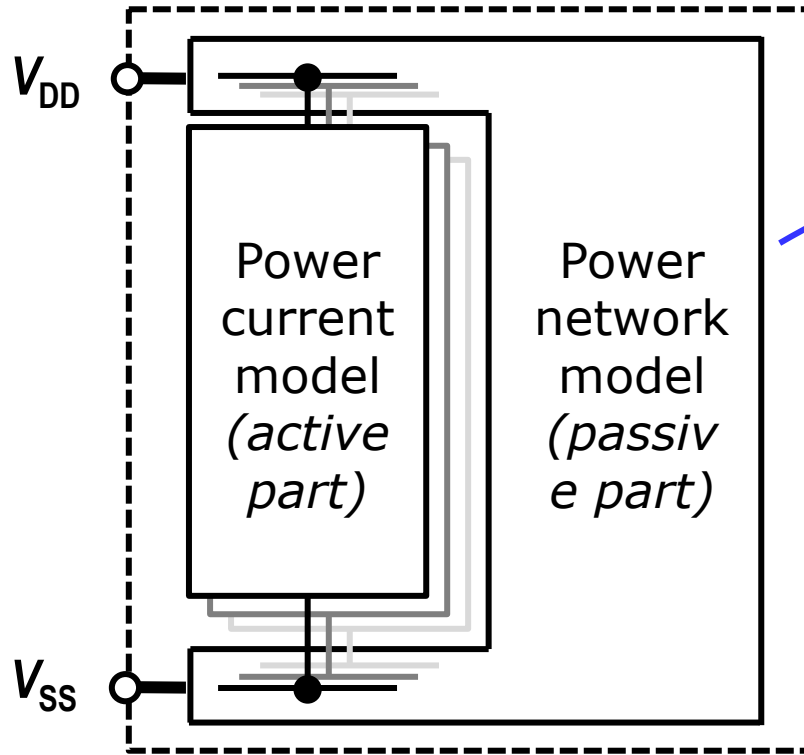
- **Si substrate** is a part of PDN (often of ground side) and the most prominent attack surface in flip-chip assembly (e.g. BGA).

System-level power noise analysis



- **Chip-Package-System board (CPS) model** used in system level simulation of power noise generation and propagation

Chip power model

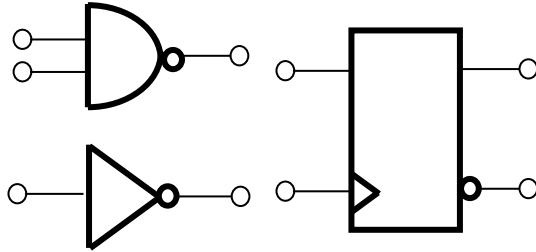


Chip power model
(CPM)
of either
"digital circuit block"
or
"whole chip"

- ▶ A power delivery network involving multiple power current models

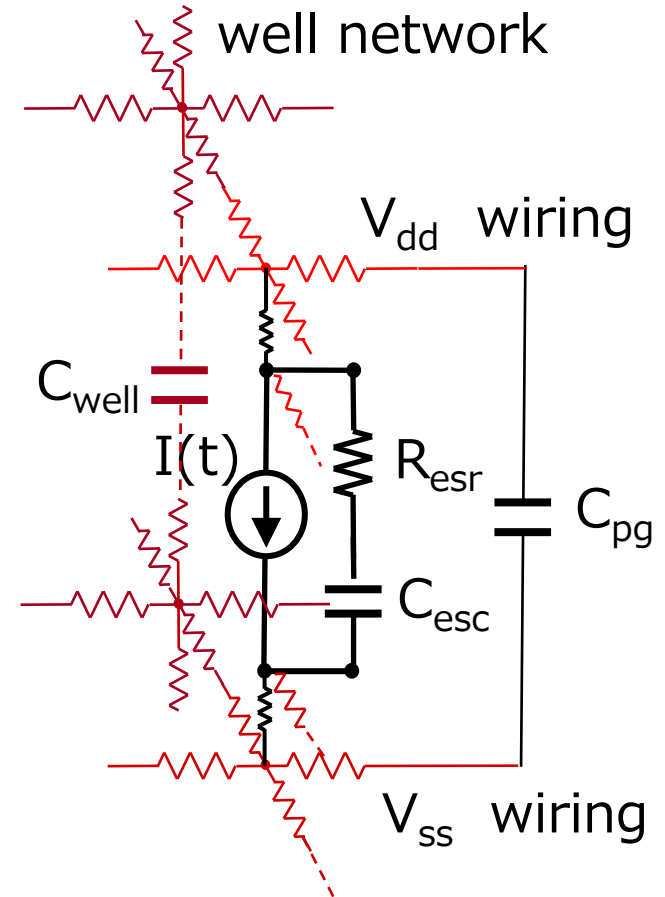
Power current - active part of model

Standard cell library (LEF/DEF)

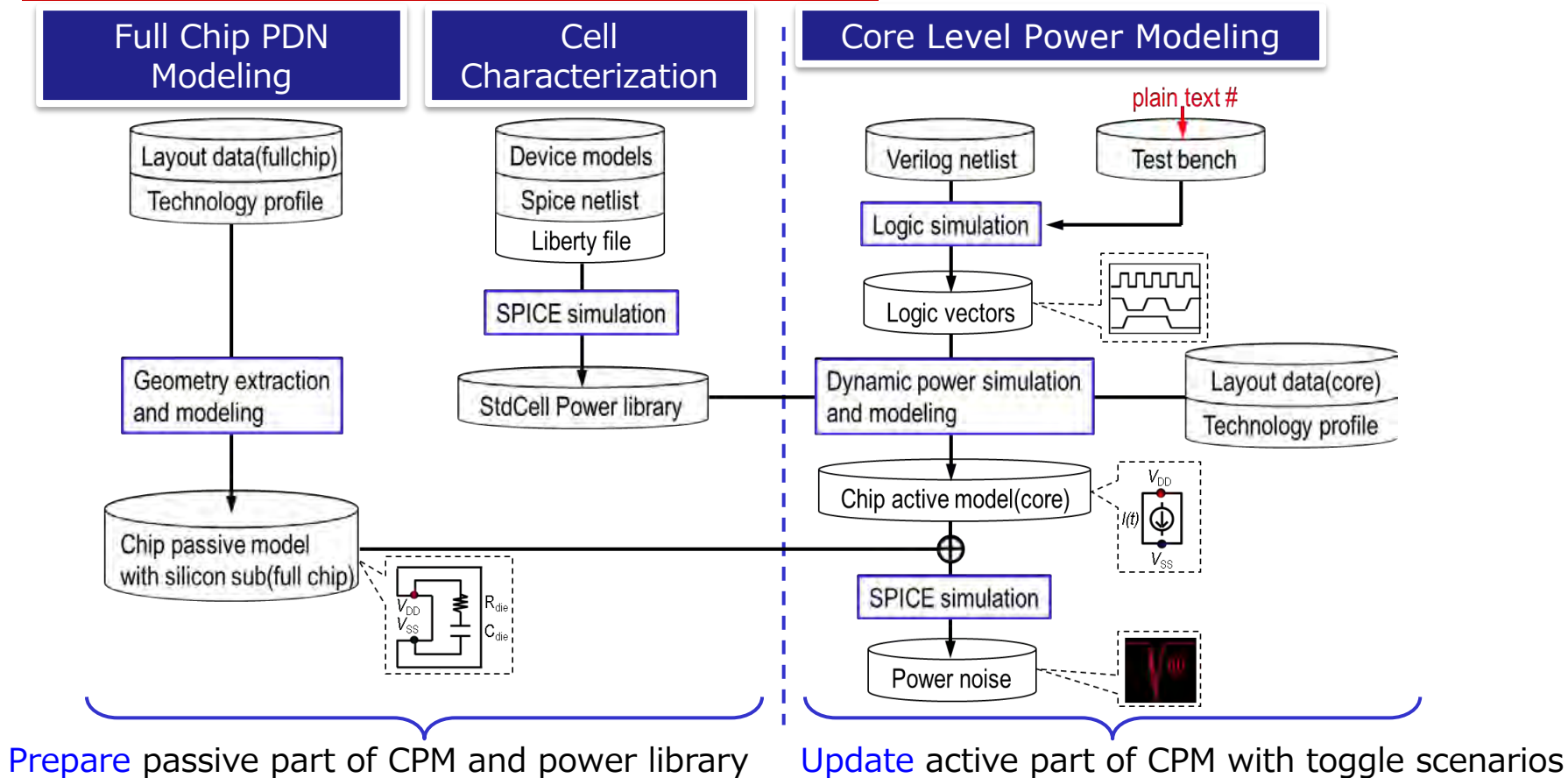


- SPICE simulation: $I(t)$
LUT for in/out condition, load caps
- Post-layout extraction
logic cell level: C_{esc} , R_{esr}

► Cell based -- Logic cells are characterized in power current model.

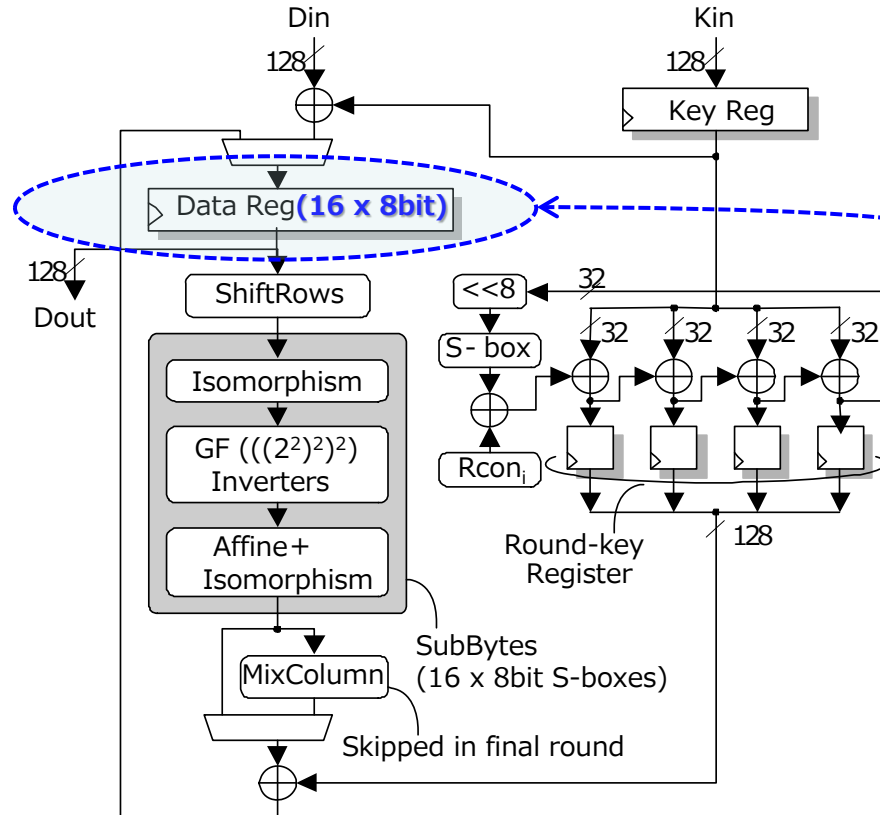


CPS power noise simulation flow



AES* cryptographic architecture

*Advanced Encryption Standard

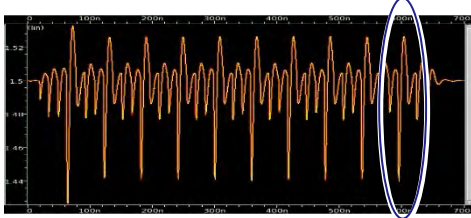


Power side-channel (SC) leakage in AES datapath

- ▶ A single key byte (8 bit) is used in byte-wise crypto computation.
- ▶ For a 128-bit key, 16 computations running in parallel
- ▶ Correlation of power current and internal activity measured as Hamming distance in a data register

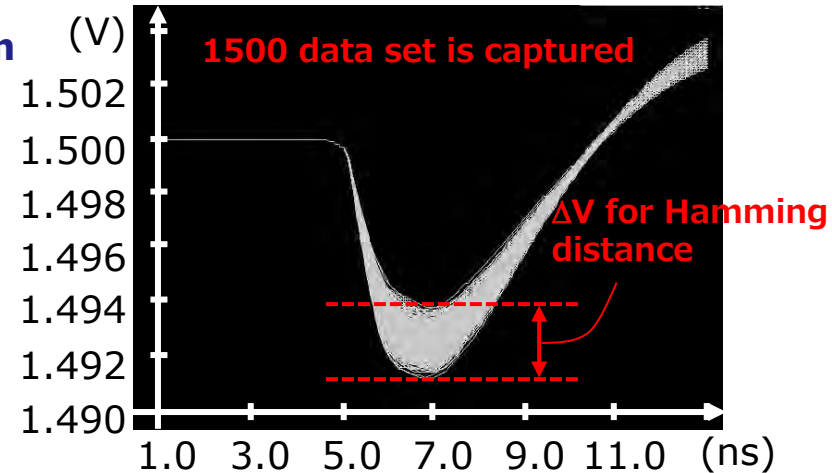
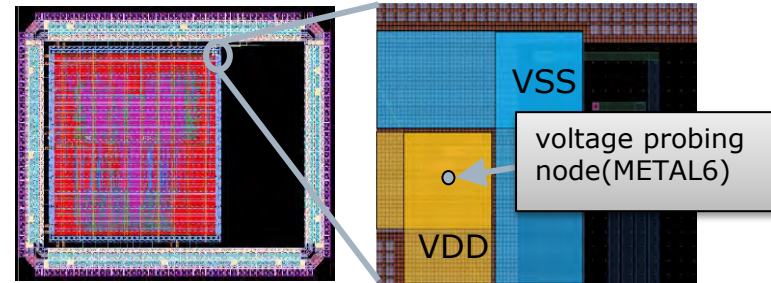
AES power noise simulation

- ▶ Case study: private-key crypto IC chip
 - ✓ AES encryption engine (34 K gates)
 - ✓ Operation frequency: 34 MHz
- ▶ Power noise on VDD during crypto operation of last round (12 ns) in CPS simulation
 - ✓ # of plain texts: 1500 **Last round of encryption**



- ▶ Simulation cost evaluation

	Memory	Threads	CPU time
PDN modeling	2726MB	8	3.0 hour
power noise modeling	2348MB	8	8.5 min
power noise simulation	229MB	1	2.8 sec

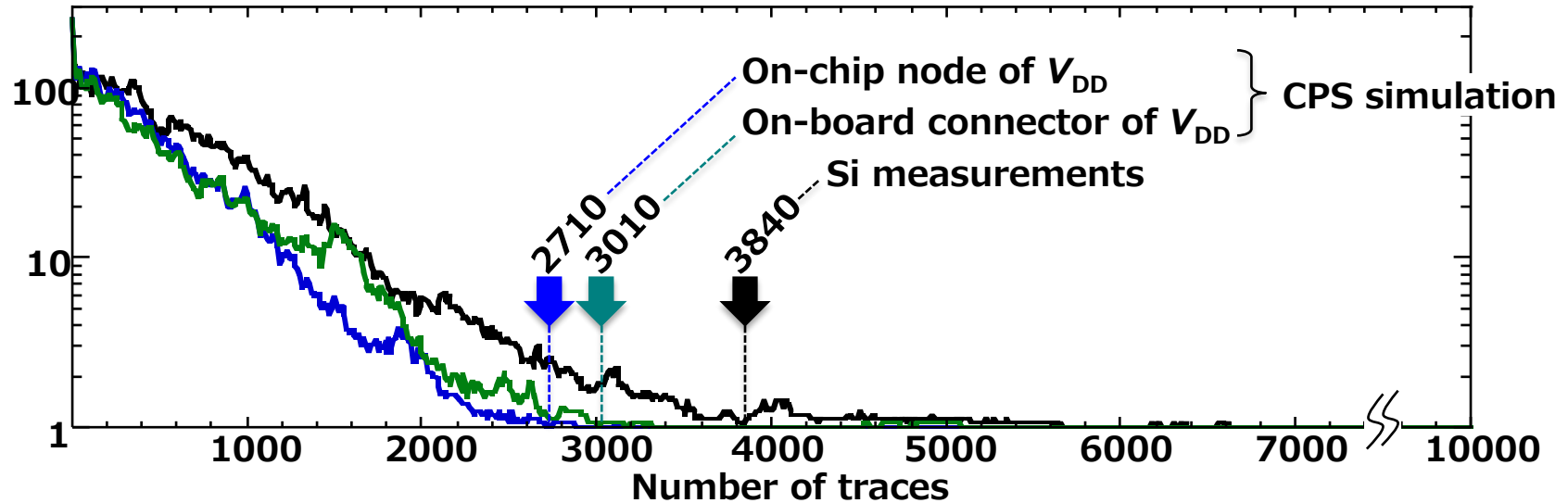


Intel Xeon CPU ES-2699 v4 (2.2GHz)

CPA on AES core

IEEE Letters on Electromagnetic Compatibility
Practice and Applications (L-EMCPA), Dec. 2019.
DOI: [10.1109/LEMCPA.2020.2978624](https://doi.org/10.1109/LEMCPA.2020.2978624)

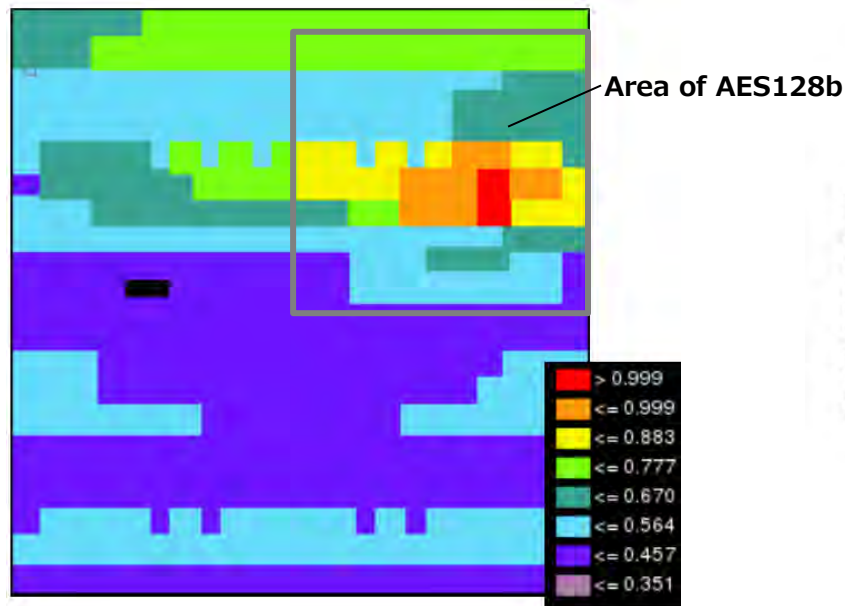
Rank of guessed key bytes



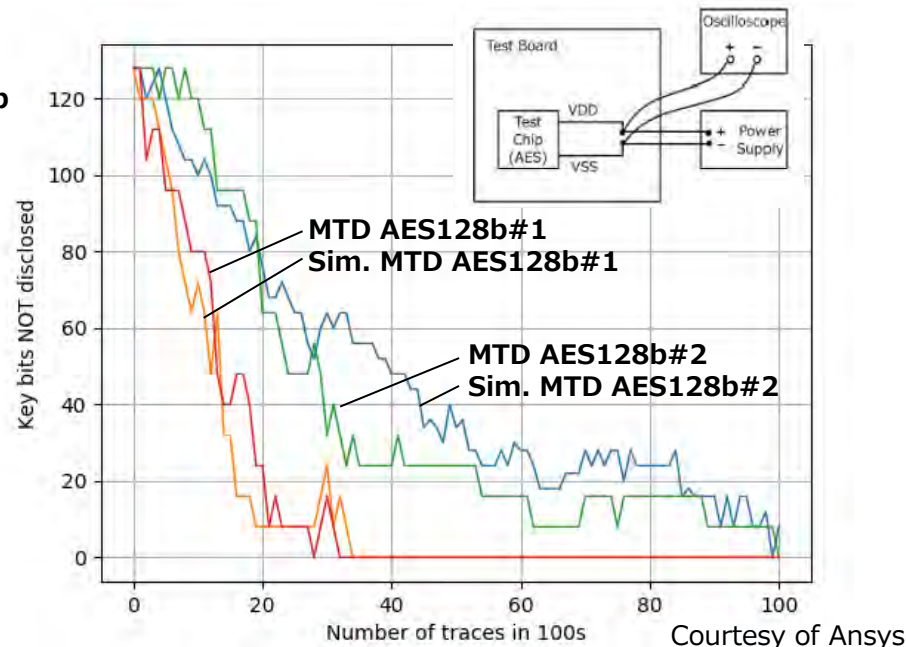
- ▶ On-chip measured and CPS simulated power traces for AES 128 bit w/ randomly generated 10k payloads
- ▶ Secret 16 key bytes are finally revealed, most pessimistic at on-chip nodes.

Power SC leakage at full-chip level

Power side-channel leakage correlation score (P-SLS)

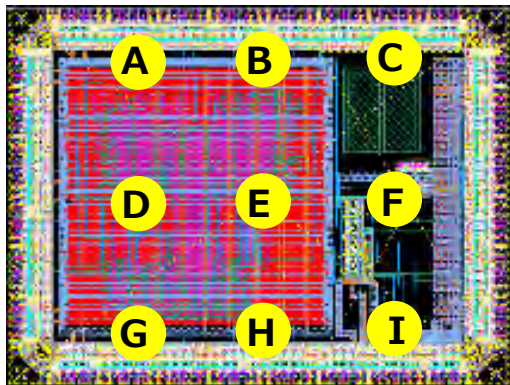


Measurement-to-disclose (MTD)



- ▶ Chip-level power SC leakage analysis using CPMs
- ▶ Direct vector control on security sensitive nets while vector-less mode on non-security nets over an IC chip.

EM SC leakage over IC chip package



Test vehicle

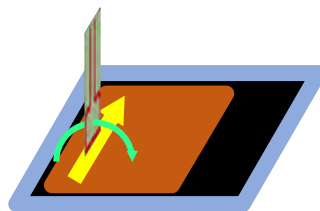
Crypto: 128bit AES

Tech.: 130 nm CMOS

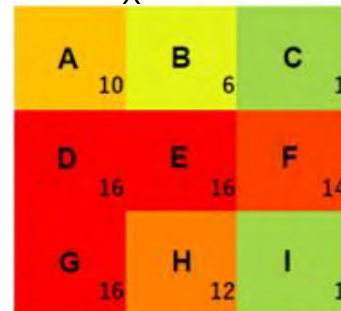
Chip area: 3 mm x 4 mm

Power supply: 1.5 V

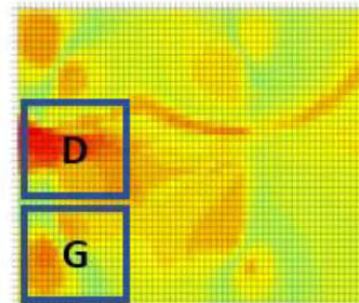
B_x Direction



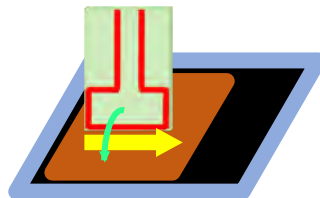
B_x Meas.



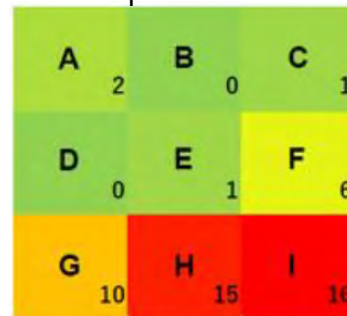
B_x Sim.



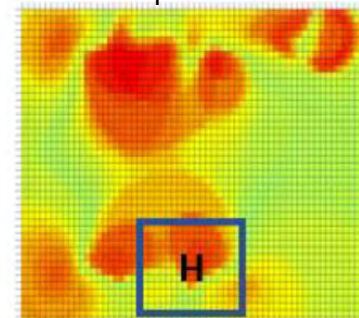
B_y Direction



B_y Meas.

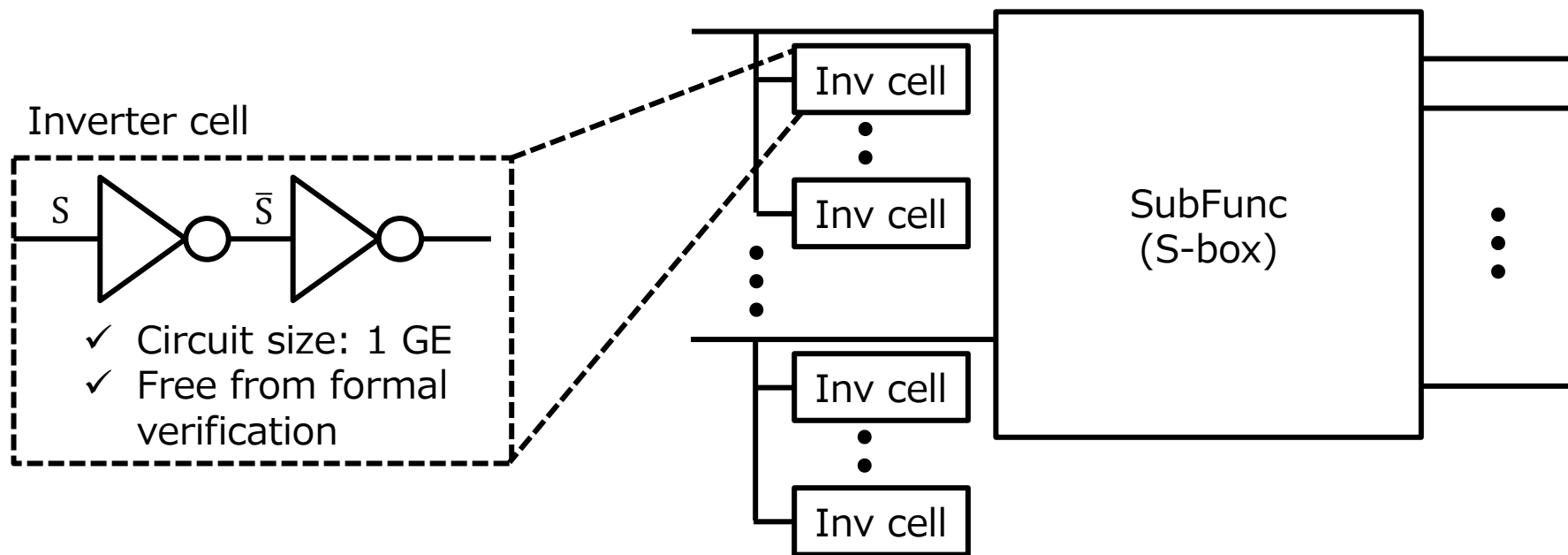


B_y Sim.



- Number of determined bytes after EM CPA for 10k random input payloads

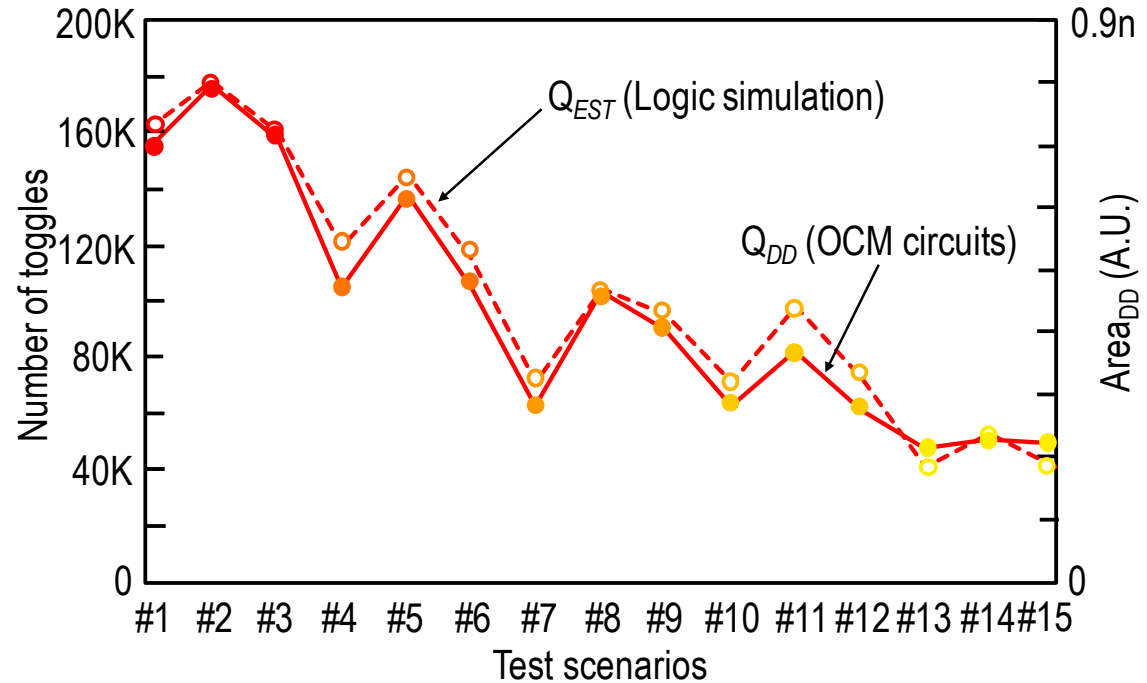
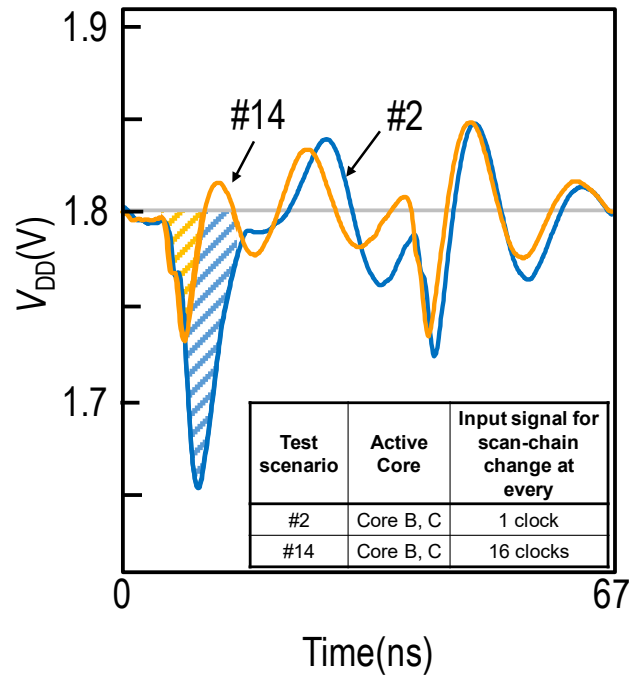
IC chip falsification with EM amplifier



- ▶ This circuit amplifies switching power, while does not change any logic.
- ▶ Neither digital FV* nor analog LVS** could find the insertion of inv. cells.

*Formal verification, **Layout versus schematic

Charge amount as indicator

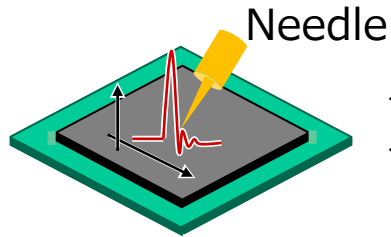


- Power (V_{DD}) waveform to estimate power current consumption, and then to be integrated over time to derive “**charge amount** (Q_{EST})” for assessments.

Outline

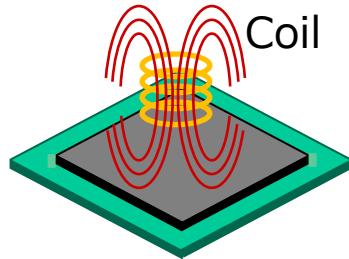
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Active fault injection on Si backside



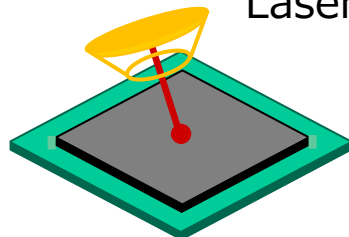
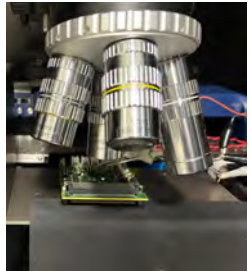
Needle

- ✓ DC biasing
- ✓ HV pulsing (High voltage)



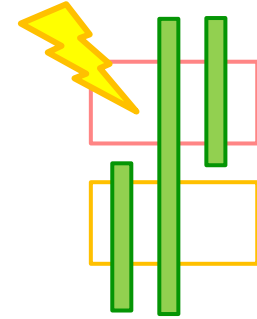
Coil

- ✓ Magnetic flux induction
- ✓ EM wave irradiation



Laser

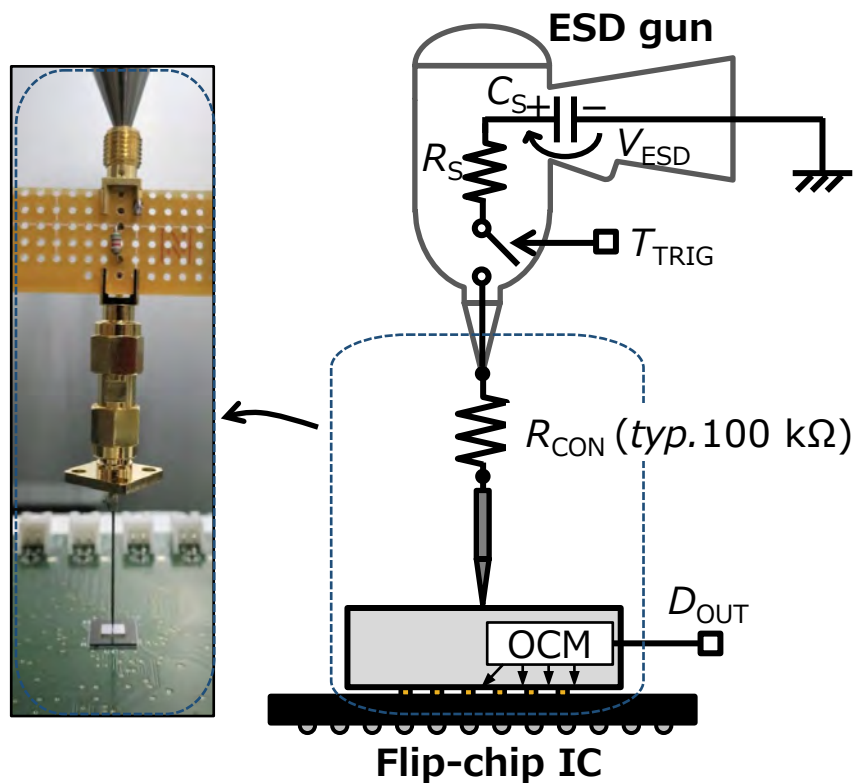
- ✓ IR laser pulsing
- ✓ HP laser drilling (High power)



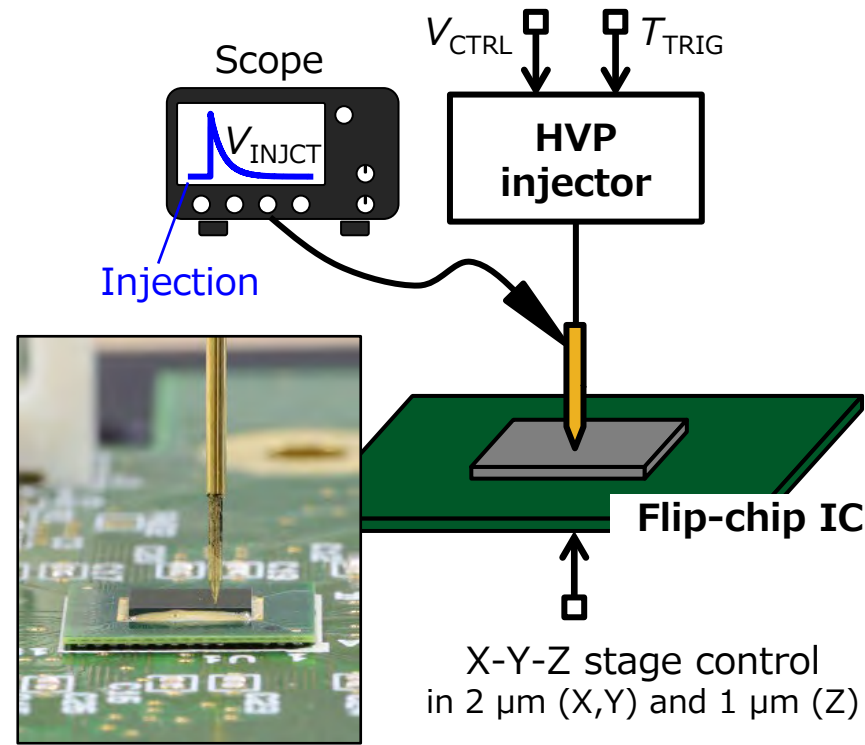
Primary physics is different.



Chip backside pulsing

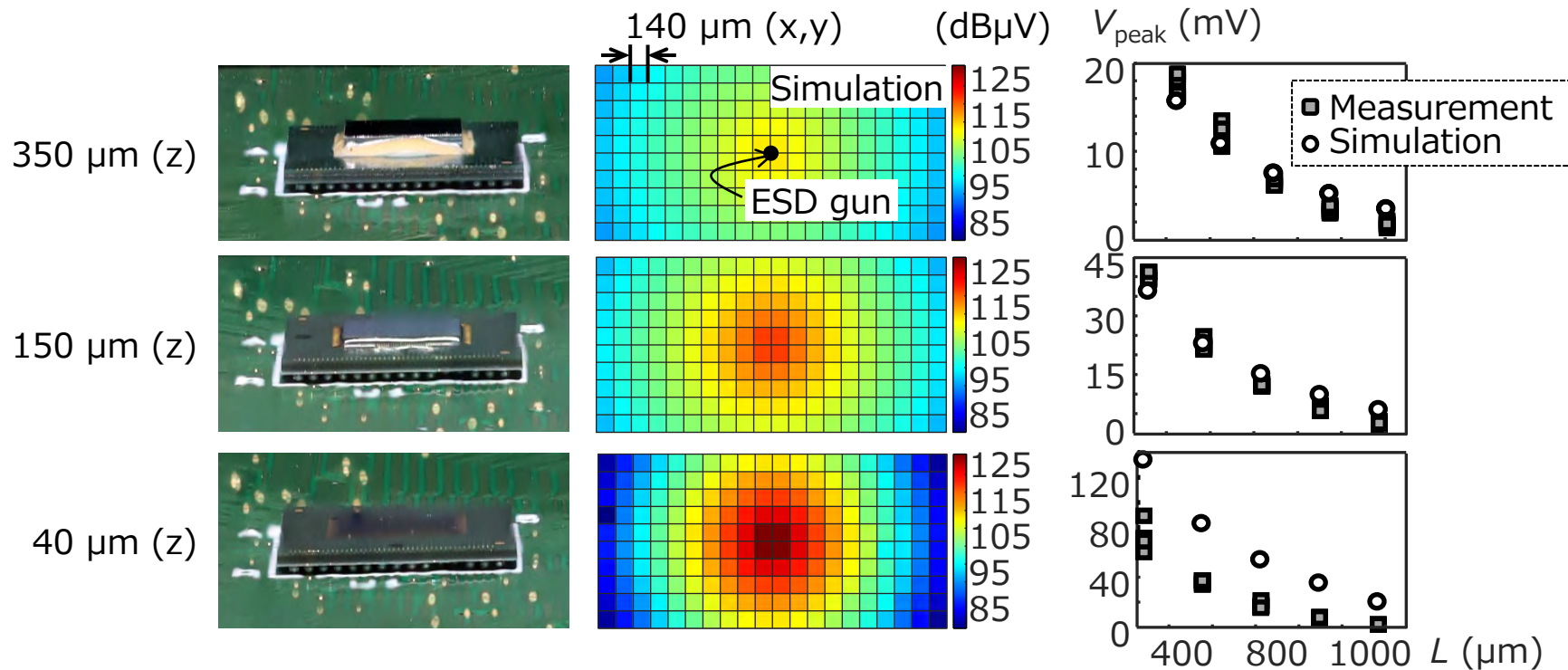


Ref. to ESD tradition (ISO10605, IEC61000-4-2)



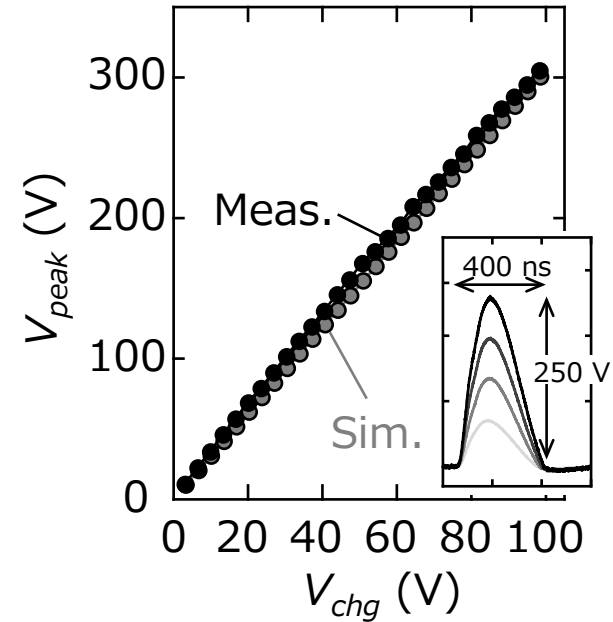
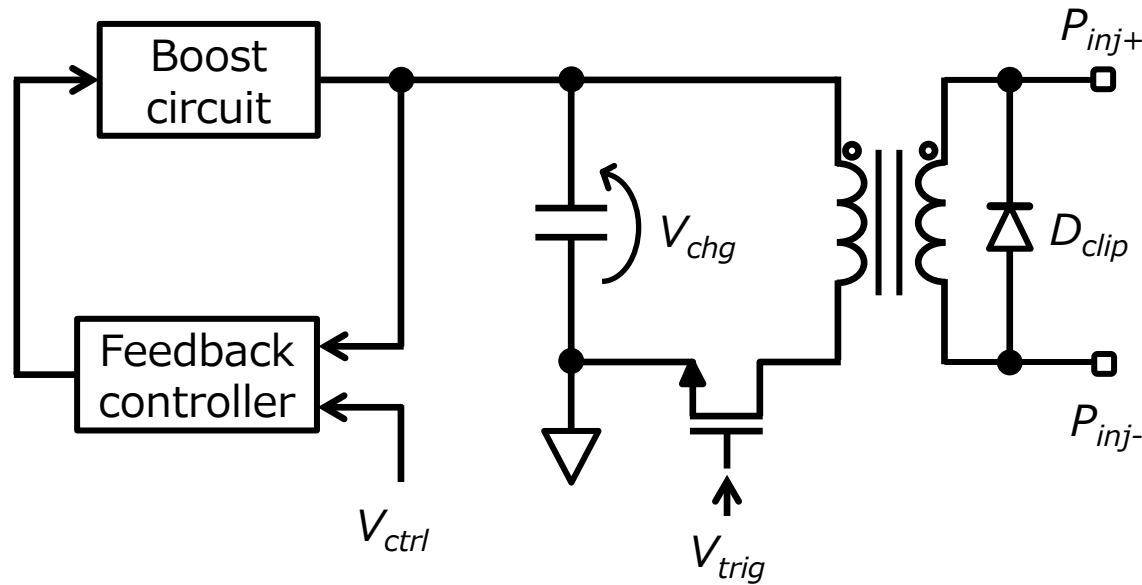
HVP injector (custom made)

Voltage spreads on IC chip frontside



- ▶ ESD gun applied on Si backside, Si voltage measured on-chip on its frontside.
- ▶ Si substrate impedance model was simulated and calibrated.

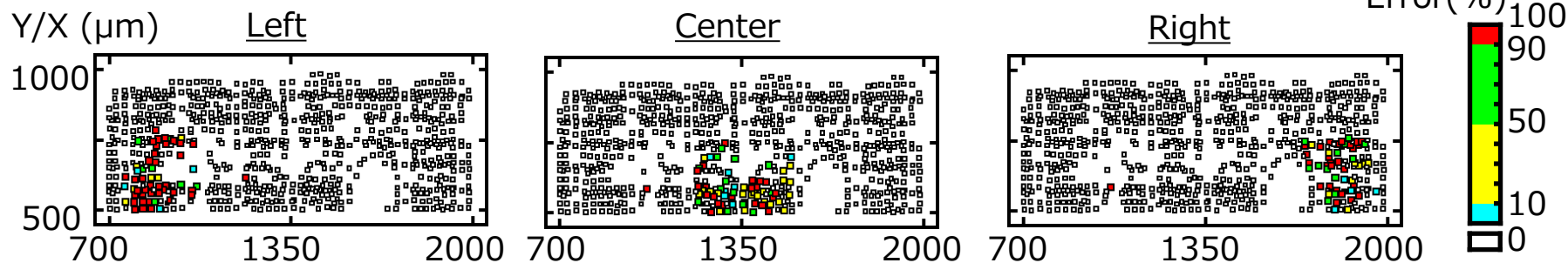
High voltage pulsing (HVP) injector



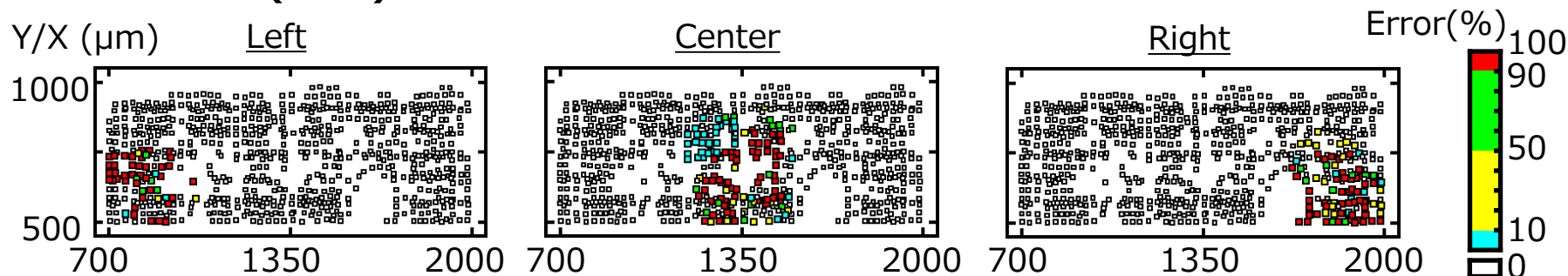
- ▶ Controllability, reproducibility and predictability of voltage pulsing in the range up to 300 V were confirmed.
- ▶ Polarity of pulsing is reversible by the connection to a needle.

Si experiments

Bit-set error (0→1)



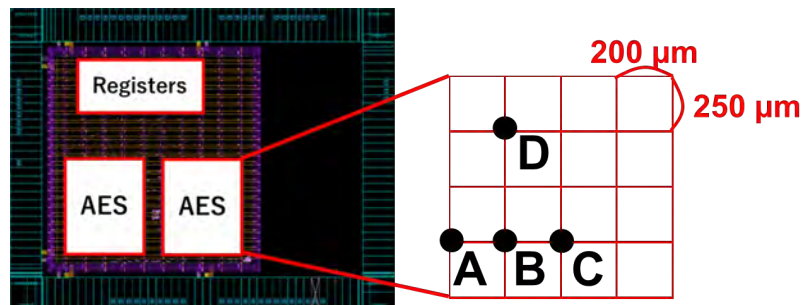
Bit-reset error (1→0)



► Error bits induced by HVP among F/Fs – strongly location dependent.

Si experiments – security threats

IEEE Fault Diagnosis and Tolerance in Cryptography (FDTC), Sep. 2024.



Si-backside HVP for DFA*

- Positive pulse : 320V
- Negative pulse : -120V

*Differential fault analysis

A

C_0	C_4	C_8	C_{12}
C_1	C_5	C_9	C_{13}
C_2	C_6	C_{10}	C_{14}
C_3	C_7	C_{11}	C_{15}

B

C_0	C_4	C_8	C_{12}
C_1	C_5	C_9	C_{13}
C_2	C_6	C_{10}	C_{14}
C_3	C_7	C_{11}	C_{15}

C

C_0	C_4	C_8	C_{12}
C_1	C_5	C_9	C_{13}
C_2	C_6	C_{10}	C_{14}
C_3	C_7	C_{11}	C_{15}

D

C_0	C_4	C_8	C_{12}
C_1	C_5	C_9	C_{13}
C_2	C_6	C_{10}	C_{14}
C_3	C_7	C_{11}	C_{15}

Faulty ciphertext with **single-bit error in every byte**

 Faulty byte

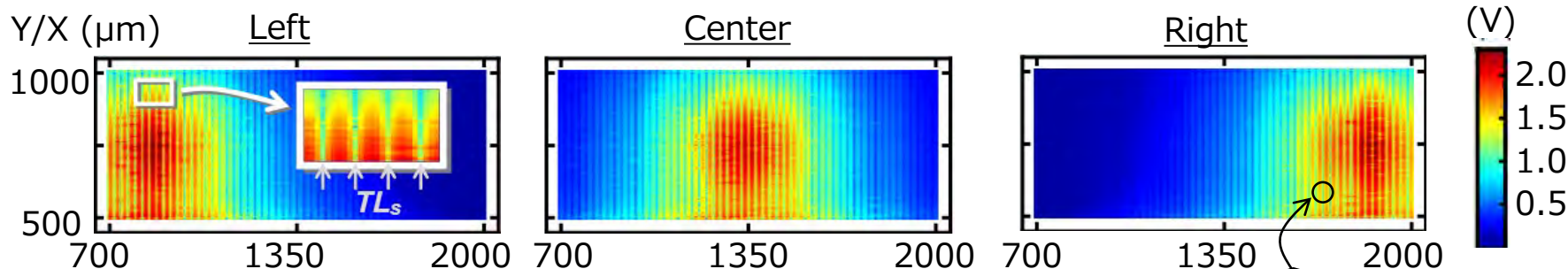
- A single bit could be intentionally flipped – alignments of placements and timing of HVP injection w.r.t. the operation of AES crypto engine.

Simulated voltage distribution

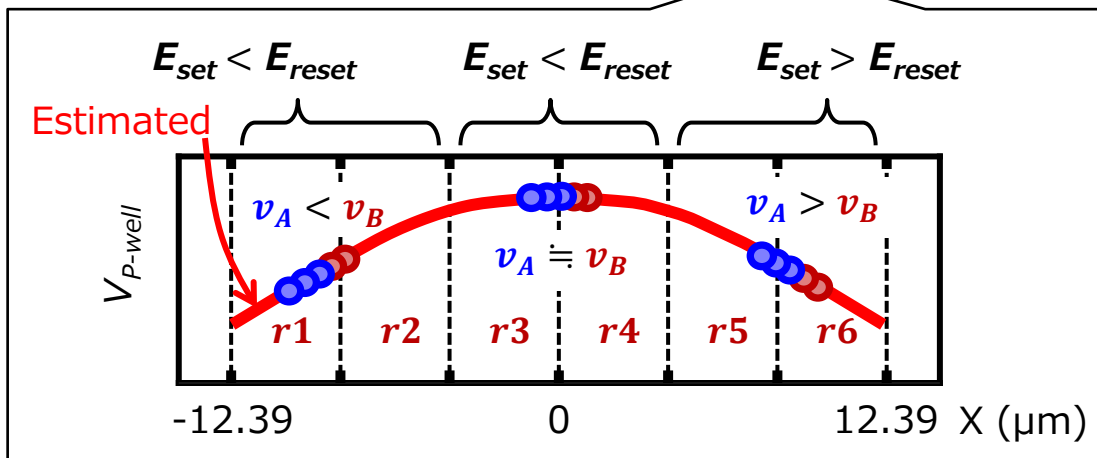
IEEE Transactions on Electromagnetic Compatibility (TEM C), Oct. 2024.

DOI: [10.1109/TEM C.2024.3440919](https://doi.org/10.1109/TEM C.2024.3440919)

P_{WELL} voltage intensity map

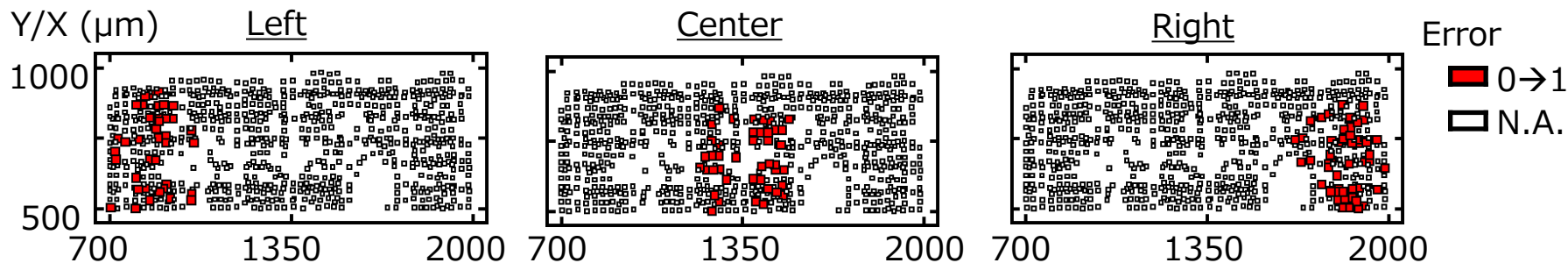


- ▶ Voltage variation at P_{WELL} level is periodically bounded by tap lines (TLs).
- ▶ Analysis regions (r1:r6) with equal interval are placed between adjacent TLs of approximately $25 \mu\text{m}$.

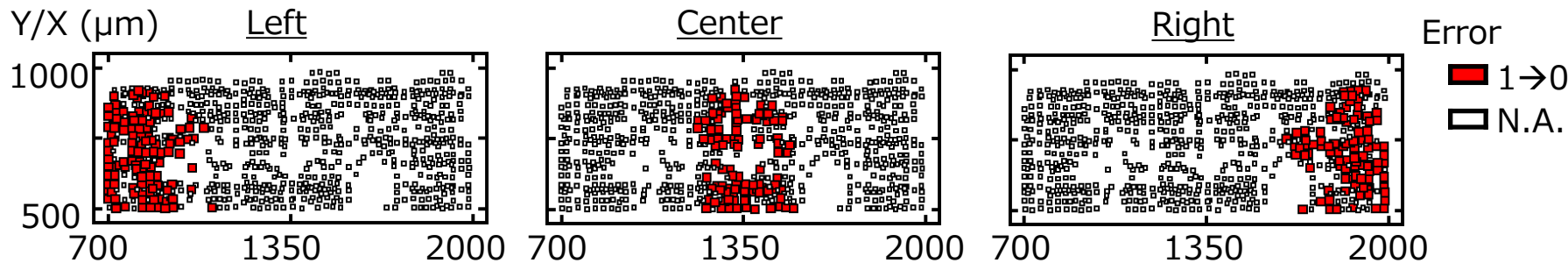


Simulation results

Bit-set error (0→1)

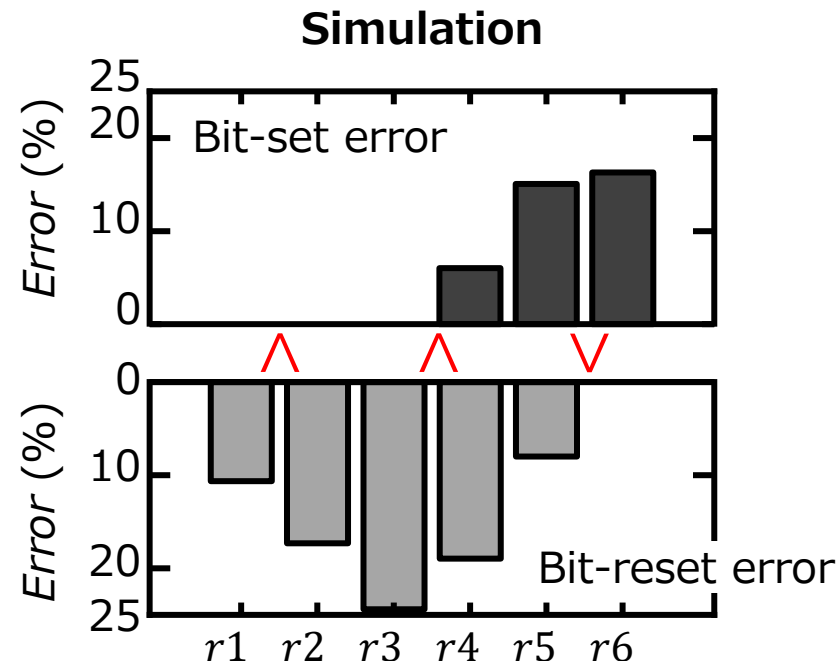
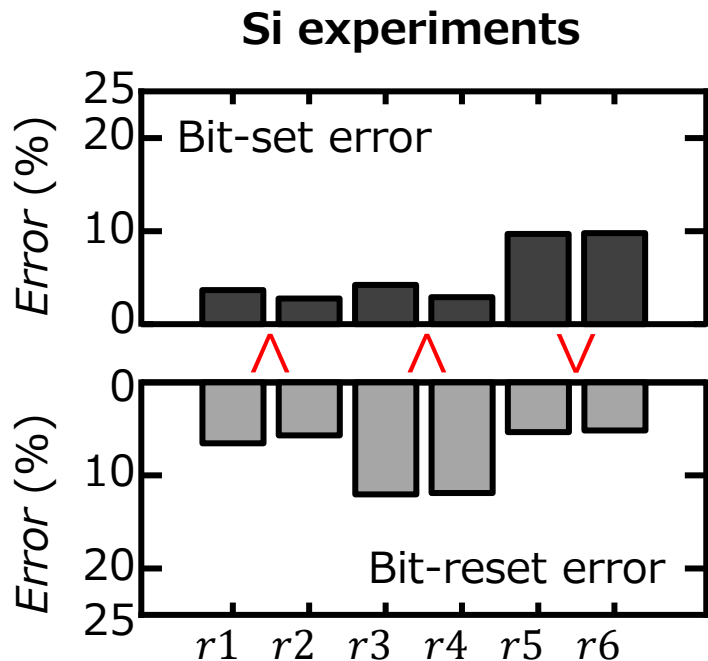


Bit-reset error (1→0)



► Location dependency and asymmetry among bit-set/bit-reset errors

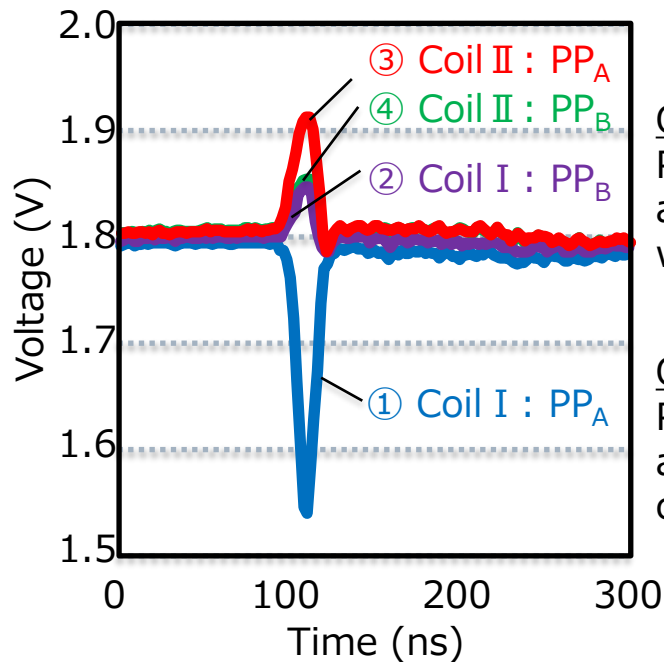
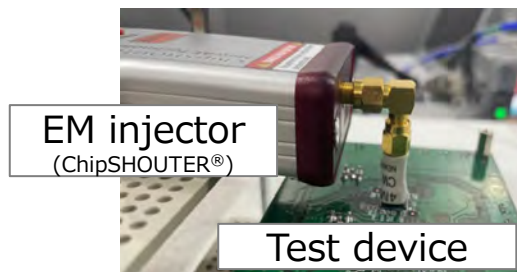
Si experiments vs. simulation



- Simulation explains **the presence of asymmetry** among the bit-set/bit-reset errors and the regions about error occurrences.

EM induced voltage on Si backside

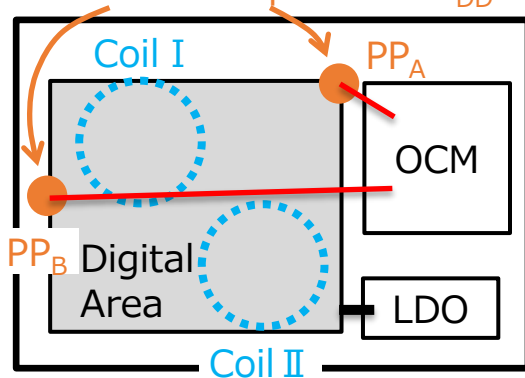
International Workshop on Constructive Side-Channel Analysis and Secure Design (COSADE), Apr. 2024.



Observation #1 (from ① vs. ②)
Positive and negative swings are observed in PP_A and PP_B when **Coil I** is used.

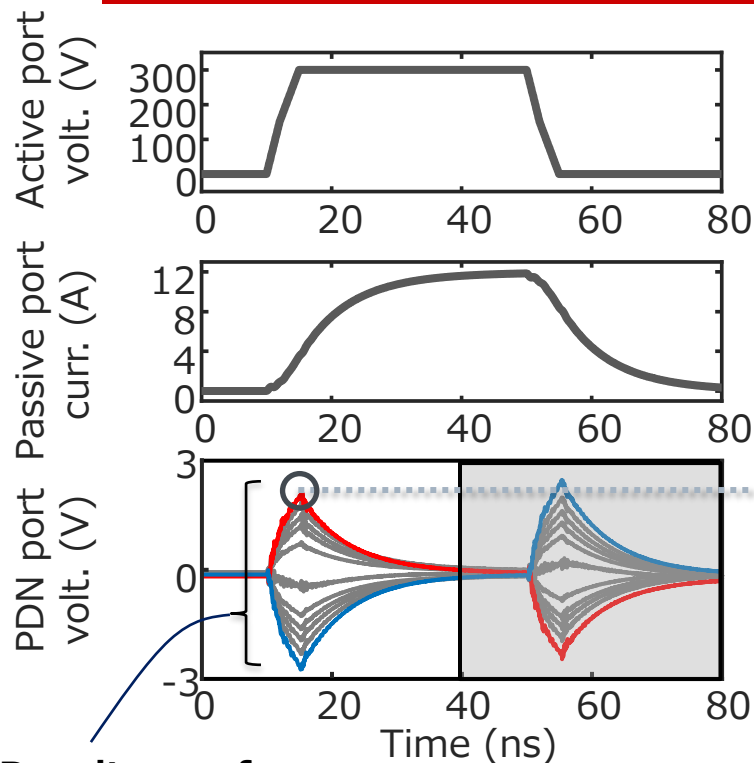
Observation #2 (from ① vs. ③)
Positive and negative swings are observed in PP_A when comparing **Coil I** and **Coil II**.

Different monitor point on V_{DD} net



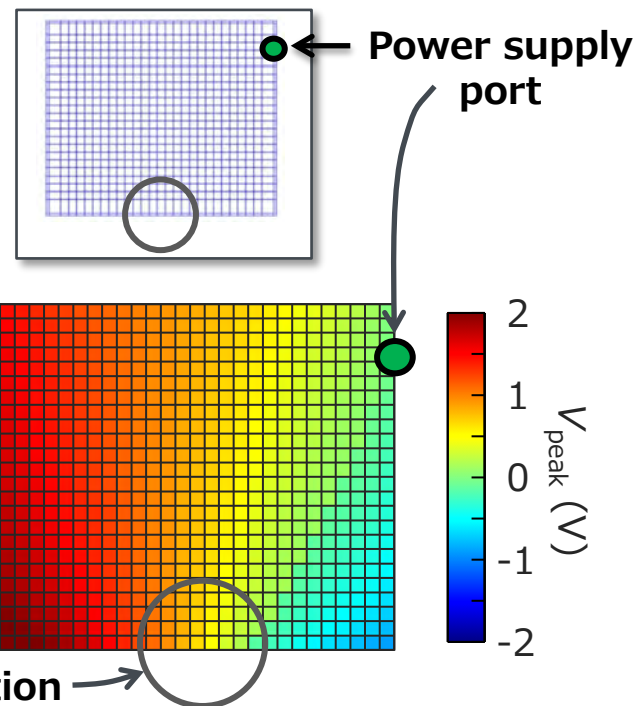
► EM fields create voltage glitches that spread across wide chip area.

Simulation of magnetic field coupling



① Extract the V_{peak} of each waveform
(At first peak, 0 ~ 40ns)

② Generate a color map based on the V_{peak} at each PDN location

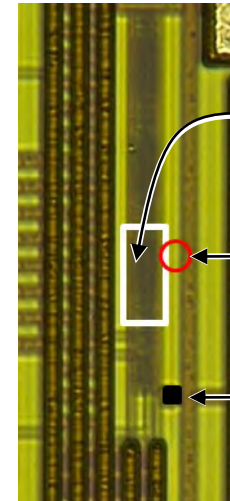
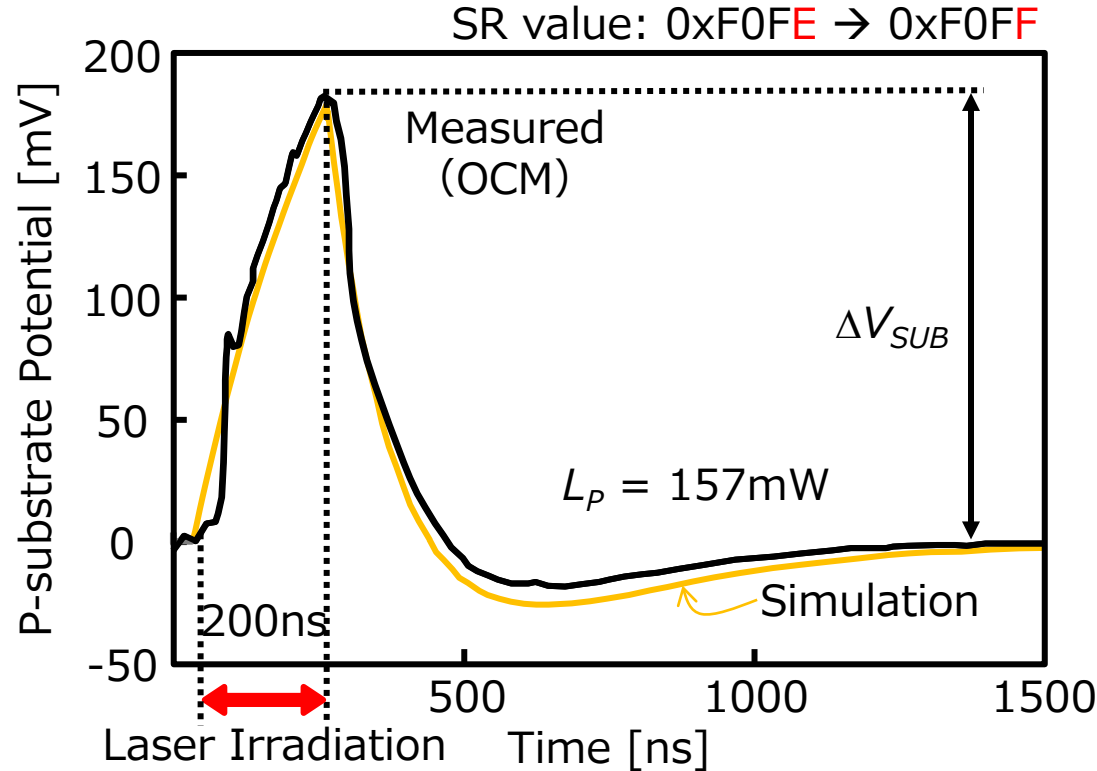


Result waveforms

$$28 \times 24 = 672$$

► Simulation explains the presence of pos. and neg. drops with physical position dependency.

Laser induced V_{SUB} waveforms



1bit Flip-Flop in
Shift Register (SR)

Laser Injection Spot

OCM Probing Point

- Simulation with equivalent circuits estimates photo-voltage conversion.

Lack of models

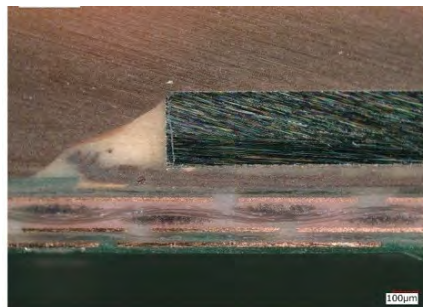
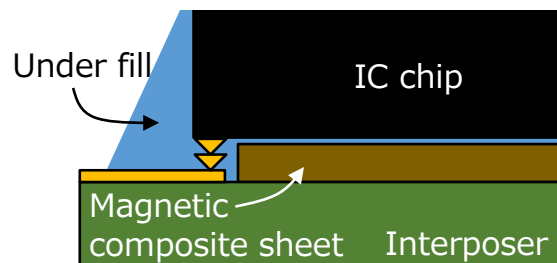
- ▶ Vertically integrated models of failures - material, device, circuits and systems – need to be explored.

Outline

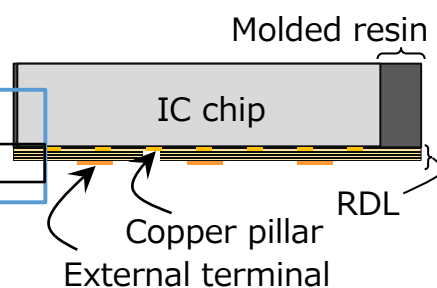
1. Introduction
2. Passive side channels from IC chip backside
3. Active fault injection on IC chip backside
4. Packaging for security
5. Summary

EM noise suppressors

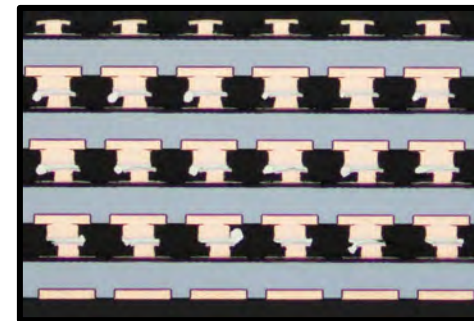
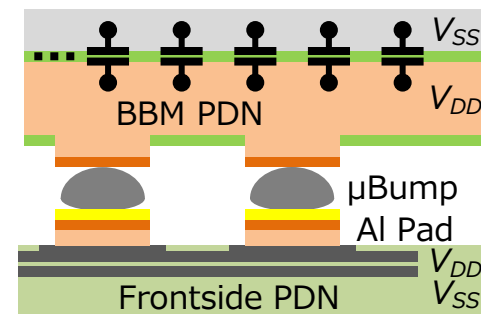
Flip-chip packaging with magnetic materials (EM power absorption)



Fan-out laminates embedding land-side capacitors



3D chip stacking with backside buried metal (BBM) capacitors



EM wave

Direct probing

IR

V_{SHD}

Top tier

Bottom tier

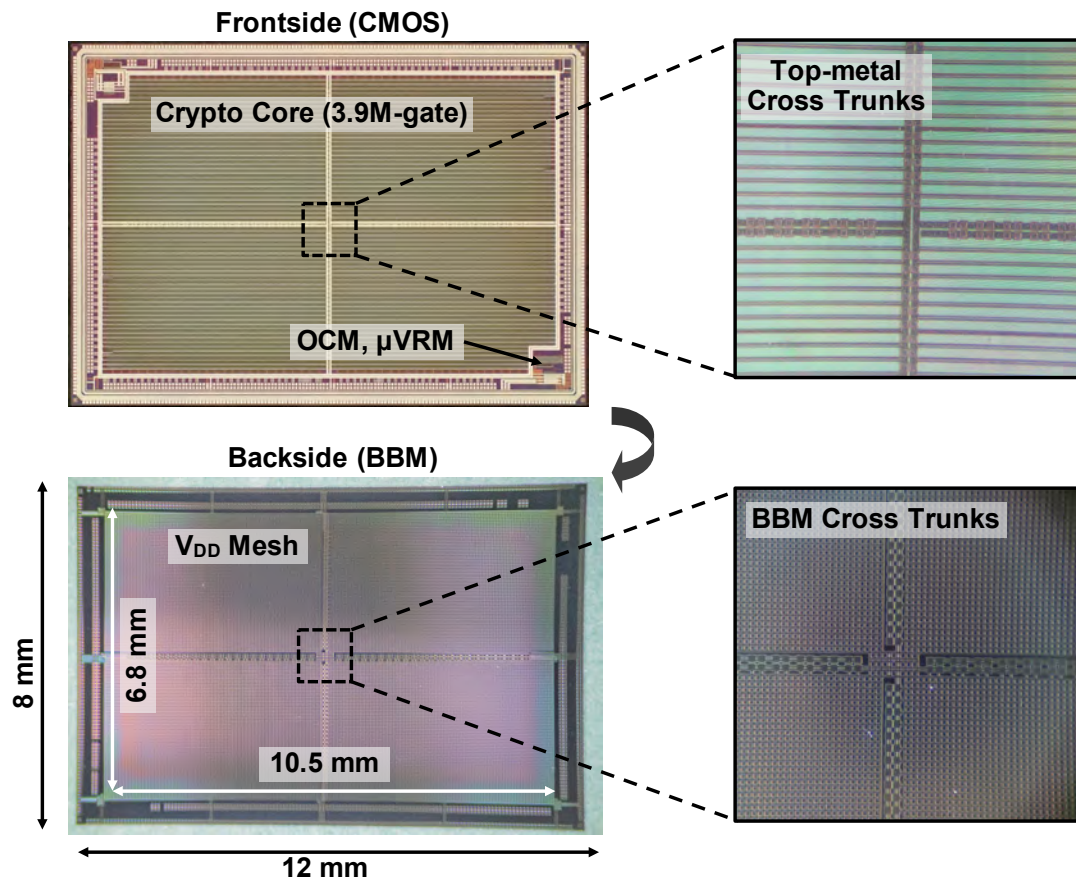
Interposer

The diagram illustrates the relationship between different components in a secure system. It consists of two main boxes. The left box is labeled 'Crypto' and contains two smaller boxes at the bottom labeled 'PMC' and 'OCM'. The right box is labeled 'Shielding (V_{SHD})' and has a yellow background with horizontal lines. A green arrow points from the top of the 'Crypto' box to the top of the 'Shielding' box, indicating a flow or dependency.

The diagram shows a 2D chip layout. On the left, there is a large white square labeled 'Crypto' with a smaller white square labeled 'PMC' in its bottom-left corner. On the right, there is a yellow square labeled 'PDN (V_{DD})' with horizontal lines.

- ▶ 3D CMOS IC chip stack with BBMs and TSVs
- ▶ Si-backside usages for safety (EM compatibility) and security (SC leakage suppression)

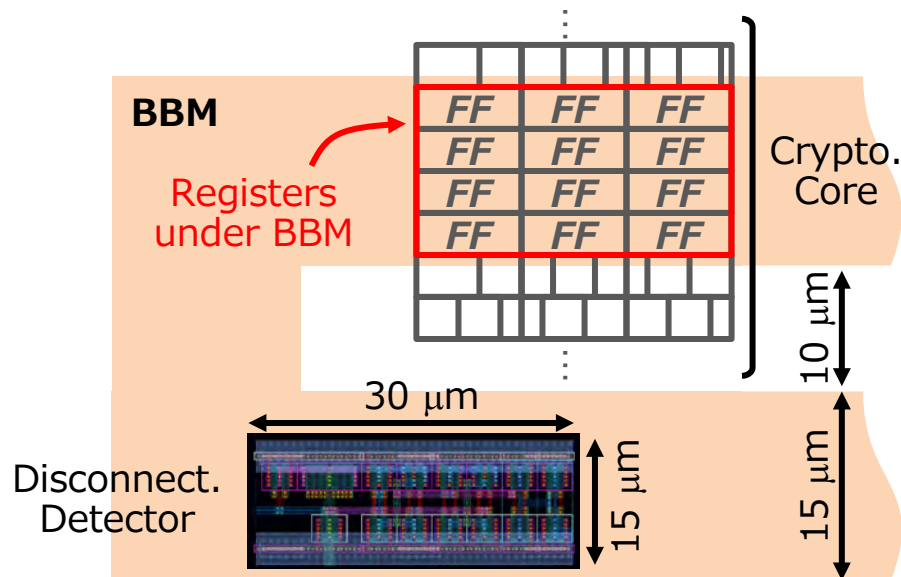
Tier photos on front and back sides



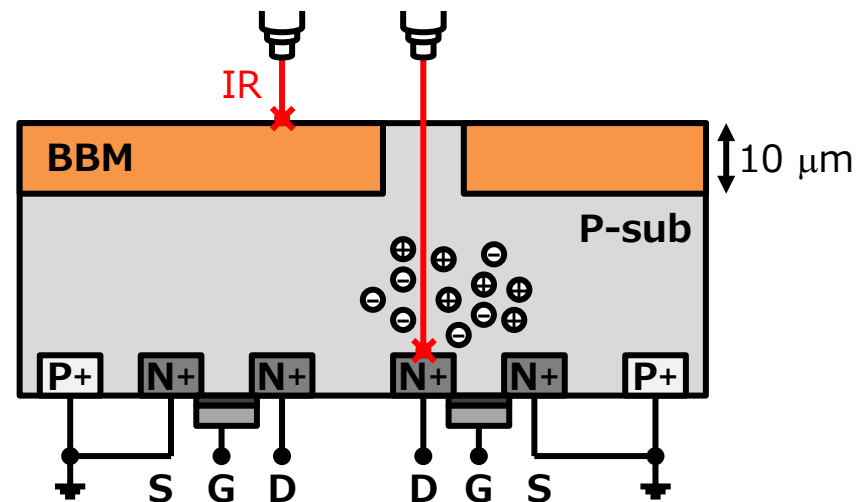
Thanks to AIST team:

Yuuki Araga
Naoya Watanabe
Haruo Shimamoto
Katsuya Kikuchi

Si-backside attack protection



Backside LFI is blocked or detected



- **Front side (IC) and back side (BBM) co-design** makes circuits of interest hidden from backside injection, as well as sensor circuits to detect injection.

Summary

- ▶ **Disciplines are common to EMC and HWS, and “good to know” in any system development.**
The knowledge is complementary among security and safety problems in general IC chips and electronic systems.
- ▶ **Analog techniques for digital security:** simulation, modeling, device, circuit, packaging and manufacturing are all to be exploited for the higher levels of HWS (and EMC.)
- ▶ **Pre-silicon assessments and design justification:** relying on advanced simulation and modeling for security and safety metrics. Theory is further needed.

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